

ABSTRACT

5           A photomask blank for a material of a photomask used in pattern transfer by  
exposure light having a wavelength of up to 250nm, including a transparent substrate, a  
chromium-containing film directly formed on the substrate or formed with an optical film  
intervened between the transparent substrate and the chromium-containing film. The  
chromium-containing film includes a region (A) composed of a chromium compound  
10 containing chromium, oxygen and carbon, wherein each of contents of the elements  
contained in the chromium compound is continuously varied in the thickness direction of  
the region (A), and toward the substrate, the content of chromium increases, and the  
content of carbon decreases.

[Fig. 1]